## 784/785 nm Dual Wavelength Narrow Linewidth Laser System of NLDM Series



Model		CL784-785-MIF(FP)-500-500mW-NLDM001
	Central Wavelength (nm)	785/784
	Output Power (mW)	> 500 (each wavelength)
	Wavelength Tolerance (nm)	± 0.5
Optical Parameter	Line Width (nm)	<0.1
	Wavelength Stability	± 0.005nm @ 8H Typ
	Power Stability	±1.0%@8H
	Side Mode Rejection Ratio (dB)	40
System Parameter	Power Adjustment Range	0~100%
	Preheat Time (Min)	15
	Modulation Input	1KHz TTL or Analog signal0-5V
	Control Interface	USB, BNC
	Fiber Interface	FC/PC
	Adapted Fiber	105µm, 0.22NA
	Power Input	100-240VAC, 50/60Hz
	System Power Consumption (W)	<7
	Storage Humidity (RH)	0~80%
	Storage Temperature (℃)	0~60
	Operating Temperature (℃)	10~35
	System Weight (Kg)	2.5
	System Size (mm)	150 x 102 x 200

## DESCRIPTION

Our company has specially developed 650nm spatial output semiconductor light source for optical experiment and particle size measurement application. It has passed industrial design and batch production. The product has the advantages of compact structure, stable power, portable operation, etc., and meets the teaching and research and development needs of universities and scientific research institutions.

## **FEATURES**

- Both wavelengths can achieve line width <0.1nm
- Frequency stability better than ±0.005nm@8H
- · Constant two-wavelength frequency interval, supporting differential calculation methods
- Temperature drift <0.007nm / °C, VBG wave lock
- Built-in TEC, power stability is better than ± 1.5%
- Including host computer control, emergency stop switch, short circuit protection and other functions





Unit: mm

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## APPLICATIONS

- Confocal microscopy
- Raman spectroscopy
- Super-resolution microscopy
- Biological detection

Top View